



P/3240-110

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Bogdan Vuletic

Serial No.: 10/572,775 /

Filed: June 29, 2006

New York, New York

Date: March 16, 2007

Group Art Unit: 1742

Examiner: ---

For: PROCESS FOR INSTALLATION FOR GRANULATING SLAG

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUBMISSION

Sir:

Submitted herewith is a copy of art together with a form listing the same for the convenience of the Examiner.

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to:
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Respectfully submitted,

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Enclosures

 APPLICANT'S REPORT CITATION (Use several sheets if necessary)	Application 10/572,775	OGFS File No. P/3240-110
	Applicant Bogdan Vuletic	
	Filing Date June 29, 2006	Group Art Unit 1742

U.S. PATENT DOCUMENTS (not submitted for applications filed after 6/30/03)

Examiner Initial	Document Number	Date MM-YYYY	Name	Class	Sub-class	Filing Date If Appropriate
	US-					
	US-					
	US-					
	US-					
	US-					
	US-					
	US-					
	US-					
	US-					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM-YYYY	Country	Class	Sub-class	Translation	
						Yes	No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Radoux, H. et al. The New System for Producing Granulated Slag with Continuous Filtering and Conveyance, <i>Fachberichte Huttenpraxis Metallweiterverarbeitung</i> , Vol. 20, No. 10, pp. 744-745, 1982.

Examiner	Date Considered
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.